Please replace the paragraph beginning on page 2, line 3, with the following

amended paragraph:

However, until recently no thin-film heaters on aluminum or aluminum alloy

substrates have been reported. Aluminum and its alloys have a relatively high coefficient of

expansion (22-26 ppm/K) compared to the insulating layers used for steel substrates which

are in most cases enamel-based insulators. Insulating layers commonly used for steel

substrates cannot be used for aluminum (alloy) substrates. Mismatched thermal expansion

coefficients result in cracking of the film when the heating element is exposed to

temperature cycles. Furthermore, in order to apply these insulators, the precursors are

applied on a suitable substrate, after which the precursor has to be cured at high

temperatures above 650 °C in order to obtain a suitable insulating layer. These high curing

temperatures exceed or are near to the melting temperature of aluminum (660 °C) and its

alloys. Therefore, these materials are not suitable as electrically insulating layers for

aluminum substrates.

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4